

The SPI Supplies Family of Instruments



Excellence in sample preparation
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Your results will never be better than your sample preparation. See how SPI Supplies can help you deliver the highest quality results for all your SEM/EDS, TEM and FESEM applications.

1. **Osmium Plasma Coaters** for FESEM Applications
2. **SPI-MODULE™** Sputter/Carbon Coater Module
3. **SC-2000™** Site-specific sample preparation for SEM
4. **Plasma Prep™ III** Solid State Plasma Cleaner for cleaning TEM holders

5. **Plasma Prep™ RIE** Anisotropic plasma etcher
6. **UV Prep** for SEM
7. **Plasma Prep™ III** Plasma Etcher with **PPIII Process Controller**
8. **Vacu Prep™ II** Turbo Pump Evaporation System
9. **SPI-DRY™** Critical Point Dryer
10. **Precision Spin Coater** Spin coater



SPI Supplies Division of **STRUCTURE PROBE, Inc.**

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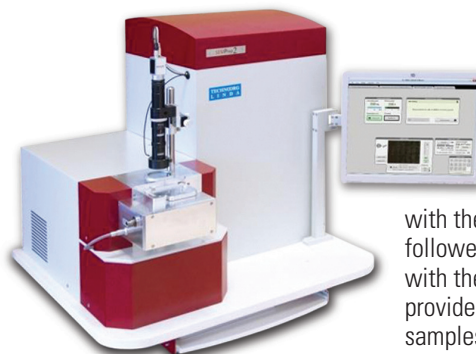


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SPI Module™ Sputter/Carbon Coaters

Combination sputter/carbon coater system for everyday routine SEM/EDS sample preparation. Fast and easy to use.



SC-2000™

Rapid slope cutting with the high-energy ion gun followed by gentle surface cleaning with the low-energy ion gun provides cross-sectional SEM samples suitable for geological, semiconductor failure analysis and other analytical purposes.



Plasma Prep™ III

Solid state compact tabletop design with RF power range of 1 to 100W. The Plasma Prep™ III Process Controller: Add-on module with multiple gas inputs and process timer control.



SPI Supplies UV Prep™ for SEM

Uses a customized UV source to effectively attack and break up hydrocarbon bonds. The result is a surface free of hydrocarbon contamination for SEM examination.

SPI Plasma Prep™ III Plasma Cleaner

Compact bench-top sized plasma cleaner, that uses the "dry plasma process" for the removal of contamination on the TEM specimen stages

SPI Supplies Vacu Prep™ II

Fast, clean, efficient, turbo-pumped, high vacuum bench-top evaporator with simple automated operation for evaporation or sputtering.



SPI PlasmaPrep™ RIE

The Plasma Prep Reactive Ion Etcher (RIE) uses a chemically reactive anisotropic plasma to etch and remove materials from package devices, wafers, and other substrates where a directional field is needed.



SPI-Dry™ Critical Point Dryers

Used in applications in electron microscopy as well as aerogels and MEMS, the critical point drying is a method of drying samples without collapsing or deforming the structure of wet, fragile specimens.

Osmium Plasma Coaters

The must have coater for high resolution FE-SEM work. Typical thickness of 1nm to 3nm of osmium metal, with excellent electrical and thermal conductivity and a virtually "amorphous" coating with no discernible grain structure.



The complete source for all your microscopy needs...
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